



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Thomas A. Figura, Kevin G. Donohoe, and
Thomas Dunbar

Serial No.: 09/470,650

Filed: December 22, 1999

For: USE OF A PLASMA SOURCE TO FORM A LAYER
DURING THE FORMATION OF A SEMICONDUCTOR DEVICE

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§ Group Art Unit: 2813
§
§ Examiner: Lisa Kilday
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§ Atty. Docket: 94-0280.04
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3RD INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

Certificate of Mailing

I hereby certify that this correspondence is being deposited with the
United States Postal Service with sufficient postage as first class mail in
an envelope addressed to:
Commissioner for Patents and Trademarks
Washington, DC 20231
on

Date 5-24-01

David J. Kilday
Signature

In compliance with the duty of disclosure under 37 C.F.R. § 1.56, Applicants respectfully request that this
Information Disclosure Statement be entered and that the references listed on the attached Form PTO-1449 be considered by
the Examiner and made of record. Copies of the listed references are enclosed for the convenience of the Examiner.

In accordance with 37 C.F.R. § 1.97(b), this Information Disclosure Statement is not to be construed as a
representation that a search has been made or that no other possible material information as defined in 37 C.F.R. § 1.56(a)
exists.

The following references are submitted for the Examiner's review:

U.S. Patents

<u>U.S. Patent No.</u>	<u>Issue Date</u>	<u>Inventor</u>
6,117,764	09/12/00	Figura et al.
5,950,092	09/07/99	Figura et al.

Other References

Application Serial No. 09/470,651, entitled USE OF A PLASMA SOURCE TO FORM A LAYER
DURING THE FORMATION OF A SEMICONDUCTOR DEVICE, filed December 22, 1999; Thomas A. Figura,
Kevin Donohoe, and Thomas Dunbar, inventors; attorney docket No. 94-0280.05; Preliminary Amendment filed
December 22, 1999; Amendment After the Continued Prosecution Application and Response to the Office Action dated

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April 13, 2000 filed July 13, 2000; Response to the Office Action dated September 26, 2000 filed October 5, 2000; Amendment and Response to the Office Action Dated November 21, 2000 filed May 21, 2001.

Application Serial No. 09/471,460, entitled USE OF A PLASMA SOURCE TO FORM A LAYER DURING THE FORMATION OF A SEMICONDUCTOR DEVICE, filed December 22, 1999; Thomas A. Figura, Kevin G. Donohoe and Thomas Dunbar, inventors; attorney docket No. 94-0280.03; Preliminary Amendment filed December 22, 1999; Amendment After the Continued Prosecution Application and Response to the Office Action dated June 6, 2000; Amendment and Response to the Office Action dated November 21, 2000, filed May 21, 2001.

This Information Disclosure Statement is being submitted after the mailing of the first Office Action, but before the mailing of a Final Rejection or Notice of Allowance. The Commissioner is authorized to charge the fee set forth in 37 C.F.R § 1.17(p) of \$180 and any additional fees which may be required to Micron Technology Inc. Deposit Account No.13-3092, Order No. 94-0280.04.

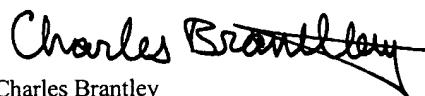
If there are any matters which may be resolved or clarified through telephone interview, the Examiner is respectfully requested to contact Applicants' undersigned attorney at the number indicated.

* * * *

A Form PTO-1449 is enclosed herewith.

Date: 5/21/1

Respectfully submitted,



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